

**CLAIMS**

WHAT IS CLAIMED IS:

1        1. A lithographic system for an integrated circuit fabrication  
2 process, the lithographic system comprising:  
3              a computer; and  
4              a configurable mask or reticle coupled to the computer,  
5 wherein the configurable mask or reticle allows light to be transmitted in a  
6 pattern controlled by a control signal from the computer.

1        2. The lithographic system of claim 1, wherein the configurable  
2 mask or reticle is an LCD or LED matrix.

1        3. The lithographic system of claim 1 further comprising:  
2              a database for providing image information associated with a  
3 device to be patterned on a wafer, the computer using the image  
4 information to generate the control signal.

1        4. The lithographic system of claim 3, wherein the database is  
2 stored on a storage media.

1        5. The lithographic system of claim 3, wherein the image  
2 information is related to transistor structures.

1        6. The lithographic system of claim 1, wherein the control  
2 signal is a video signal.

1        7. A method of manufacturing an integrated circuit, the method  
2 comprising:

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3                   providing a pattern of radiation via an LCD or LED assembly;  
4   and

5                   performing a semiconductor fabrication process in  
6   accordance with the pattern of radiation.

1         8.   The method of claim 7, further comprising:  
2                   providing a second pattern of radiation via the LCD or LED  
3   assembly; and  
4                   performing a second semiconductor fabrication process in  
5   accordance with the second pattern of radiation.

1         9.   The method of claim 7, wherein the pattern is provided to a  
2   wafer in a step and repeat process.

1         10.   The method of claim 7, wherein the pattern is representative  
2   of a metal layer associated with the integrated circuit.

1         11.   The method of claim 7, wherein the pattern is representative  
2   of a structure associated with a transistor for the integrated circuit.

1         12.   The method of claim 7, wherein a representation of the  
2   pattern is stored electronically.

1         13.   The method of claim 7, wherein the integrated circuit is an  
2   ASIC.

1         14.   The method of claim 7, wherein the pattern is provided via  
2   the LCD assembly.

1         15.   A pattern generator for an integrated circuit fabrication  
2   system, the pattern generator comprising:

3           means for providing a pattern of light; and  
4           means for controlling the means for providing, wherein the  
5       means for controlling selects the pattern.

1       16. The pattern generator of claim 15, further comprising:  
2           means for providing a light through the means for providing a  
3       pattern.

1       17. The pattern generator of claim 16, further comprising:  
2           means for focusing the light on a wafer.

1       18. The pattern generator of claim 15, further comprising:  
2           means for storing elements, wherein the means for  
3       controlling creates a control signal representative of the pattern in  
4       response to the elements.

1       19. The pattern generator of claim 15, wherein the means for  
2       controlling includes a workstation executing a software program.

1       20. The pattern generator of claim 19, wherein the means for  
2       providing a pattern includes liquid crystals.